

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Robert P. Meagley et al.

Serial No.: 10/688,521

Filed: October 17, 2003

For: Reducing Photoresist Line Edge
Roughness Using Chemically-
Assisted Reflow

§ Group Art Unit:

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§ Examiner:

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§ Atty. Dkt. No.: ITL.1026US (P16713)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT


Dear Sir:

Applicant submits the references listed on the attached form PTO 1449 together with any required copies of such references.

This statement is being filed before the receipt of a first Office action on the merits. Please apply any charges or credits to Deposit Account 20-1504.

Respectfully submitted,

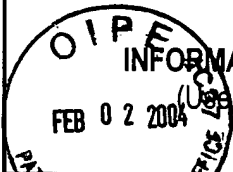
Date: January 29, 2004


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Date of Deposit: January 29, 2004

I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.


Sherry Tipton

	ATTY DOCKET NO. ITL1026US (P16713)		SERIAL NO. 10/688,521
	APPLICANT(S): ROBERT P. MEAGLEY ET AL.		
	FILING DATE: October 17, 2003	GROUP ART UNIT:	

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	A.						
	B.						
	C.						
	D.						
	E.						
	F.						
	G.						
	H.						
	I.						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	J.							
	K.							
	L.							
	M.							
	N.							
	O.							
	P.							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Q.	Robert P. Meagley and Michael D. Goodner, U.S. Patent Application Serial No. 10/679,793, filed 10/06/2003, entitled "Increasing the Etch Resistance of Photoresists"
	R.	
	S.	
	T.	
	U.	
	V.	
	W.	

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.